

**PHOTOMASK FOR FORMING PHOTORESIST PATTERNS
REPEATING IN TWO DIMENSIONS AND METHOD OF
FABRICATING THE SAME**

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ABSTRACT OF THE DISCLOSURE

A photomask includes a transparent substrate, and a plurality of light-shielding patterns repeatedly aligned on the transparent substrate in two dimensions. Each of the light-shielding patterns has length and width measurements that differ from each other. Further, the photomask includes at 10 least one through hole penetrating a portion of each of the light-shielding patterns to expose the transparent substrate.